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TITLE: PHOTOSENSITIVE RESIN COMPOSITION
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INVENTOR-INFORMATION:

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ASSIGNEE-INFORMATION:

NAME	COUNTRY
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ABSTRACT:

PROBLEM TO BE SOLVED: To provide a photosensitive resin composition capable of easily forming a micro-patterned thin film excellent in low dielectric property as well as in various properties such as flatness, heat resistance, transparency and chemical resistance.

SOLUTION: The photosensitive resin composition contains an alkali-soluble alicyclic olefin polymer obtained by modifying an alicyclic olefin polymer with a compound having an acid derivative type residue such as an amido or carboxyl group, a crosslinking agent such as an alkoxymethylated melamine or an alkoxyethylated glycol uryl and a photo-acid generating agent such

as a
halogen-containing triazine compound.

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